

REMARKS

Claims 1-35 were pending.

Claims 1-20 were rejected.

Claim 1 was objected to.

Claims 1-20 have been amended.

Claims 21-35 have been canceled without prejudice.

Claims 1-20 will be pending upon entry of this amendment;
claims 1, 16, and 19 are the only independent claims.

I. AFFIRMATION OF ELECTION

Applicants affirm the election of Group I, claims 1-20 without traverse. Withdrawn claims 21-35 have been cancelled without prejudice.

II. OBJECTIONS TO THE DRAWINGS

FIG. 4 is objected to because of inconsistencies between the drawing and Applicants' Specification. Accordingly, replacement FIG. 4 is included to properly indicate reference numeral 401b.

III. CLAIM OBJECTIONS

Claim 1 was objected to because SRD was not written out fully in the claims. Accordingly, Applicants have amended claims 1-20 to write out 'SRD' as 'Spin Rinse Dryer'. No new matter has been added by these amendments. The amendments to claims 1-20 are not intended to narrow the scope of the claims.

IV. CLAIM REJECTIONS - 35 U.S.C. § 103

Claims 1-8, 11, and 13-20 are rejected under 35 U.S.C. § 103(a) as being unpatentable over Japanese Patent Publication

No. JP2001007068 ("White") in view of U.S. Patent No. 5,762,748 ("Banholzer") or U.S. Patent No. 6,162,297 ("Mintz").

Applicants respectfully traverse this rejection.

The Examiner states that White discloses a substrate support, fluid source, and shield. However, the Examiner states that White does not specifically disclose the shield has a particle-blasted finish and points to Mintz and Banholzer, apparently to show the particle-blasted finish.

Applicants respectfully submit that there is no motivation to combine either Mintz or Banholzer with White. Mintz appears to describe *CVD and PVD processing chambers* which may have grit blasted surfaces on the components thereof to prevent flaking of deposition material. See, for example, Mintz, Col. 1, lines 14-29 and 46-67. Banholzer appears to describe a shield for a *vacuum chamber* (e.g., a chamber "to etch and deposit thin films and form contacts in semiconductor substrates during manufacturing of, inter alia, integrated circuits" (Banholzer, Col. 1, lines 15-17)). Neither the Mintz or Banholzer shield is for use in a spin rinse dryer.

In contrast to Mintz and Banholzer, the shield in the *spin rinse dryer* of the present invention is designed "to receive fluid thrown off by a substrate which is rinsed and spun within the SRD" (Applicants' Specification, Page 4, lines 19-20) and may be particle-blasted "so as to exhibit a hydrophilic characteristic or to increase the hydrophilic characteristic of an already hydrophilic surface" (Applicants' Specification, Page 4, lines 23-25). The shields of Mintz and Banholzer are not designed for the same use, nor are they used in the same equipment. Applicants respectfully submit that one of ordinary skill would not be motivated to particle blast the shield of a spin rinse dryer to adjust/create hydrophilic surface properties

for the shield because of the disclosure in Mintz or Banholzer, which describe shields for use in deposition environments.

Accordingly, Applicants respectfully submit that independent claims 1, 16, and 19 and dependent claims 2-8, 11, 13-15, 17-18, and 20, which depend therefrom, are patentable over the cited references and respectfully request the Examiner reconsider and withdraw this rejection.

Claims 9, 10, and 12 are rejected under 35 U.S.C. § 103(a) as being unpatentable over White in view of Banholzer or Mintz and further in view of U.S. Patent No. 5,476,520 ("Jaffe"). Applicants respectfully traverse the rejection.

Dependent claims 9, 10, and 12 inherit the features of patentable claim 1, as described above. Jaffe does not appear to overcome the deficiencies of the above-discussed references. For at least the reasons cited above with respect to independent claim 1, from which dependent claims 9, 10, and 12 depend, Applicants respectfully submit that claims 9, 10 and 12 are patentable over the cited references and respectfully request the Examiner reconsider and withdraw this rejection.

V. DOUBLE PATENTING REJECTION

Claims 1-8, 11, and 13-20 are rejected on the ground of nonstatutory obviousness type double patenting as being unpatentable over claims 1, 5-8, 11-15, 17, 24-26, 32, 33, 38-41, and 47 of U.S. Patent No. 6,516,816 ("Husain") in view of U.S. Patent No. 5,762,748 ("Banholzer") or U.S. Patent No. 6,162,297 ("Mintz"). Applicants respectfully traverse this rejection.

As discussed above with respect to the 35 U.S.C. § 103(a) rejection of claims 1-8, 11, and 13-20, Applicants do not believe there is motivation to combine the teachings of Mintz or Banholzer with that of the White reference. Likewise,

Applicants respectfully submit that there is no motivation or suggestion to combine the teachings of Husain with that of Mintz or Banholzer.

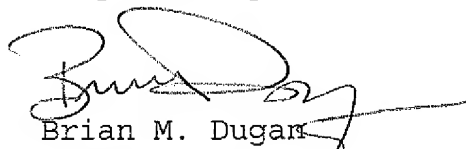
Accordingly, Applicants respectfully submit that independent claims 1, 16, and 19 and dependent claims 2-8, 11, 13-15, 17-18, and 20, which depend therefrom, are patentable over the cited references and respectfully request the Examiner reconsider and withdraw this rejection.

VI. CONCLUSION

The Applicants believe all the claims are now in condition for allowance, and respectfully request reconsideration and allowance of the same.

A Request for Extension of Time is submitted herewith, with authorization to charge the requisite extension fee to Deposit Account No. 04-1696. Applicants do not believe any other fees are due regarding this amendment. If any other fees are required, however, please charge Deposit Account No. 04-1696. The Applicants encourage the Examiner to telephone Applicants' attorney should any issues remain.

Respectfully Submitted,



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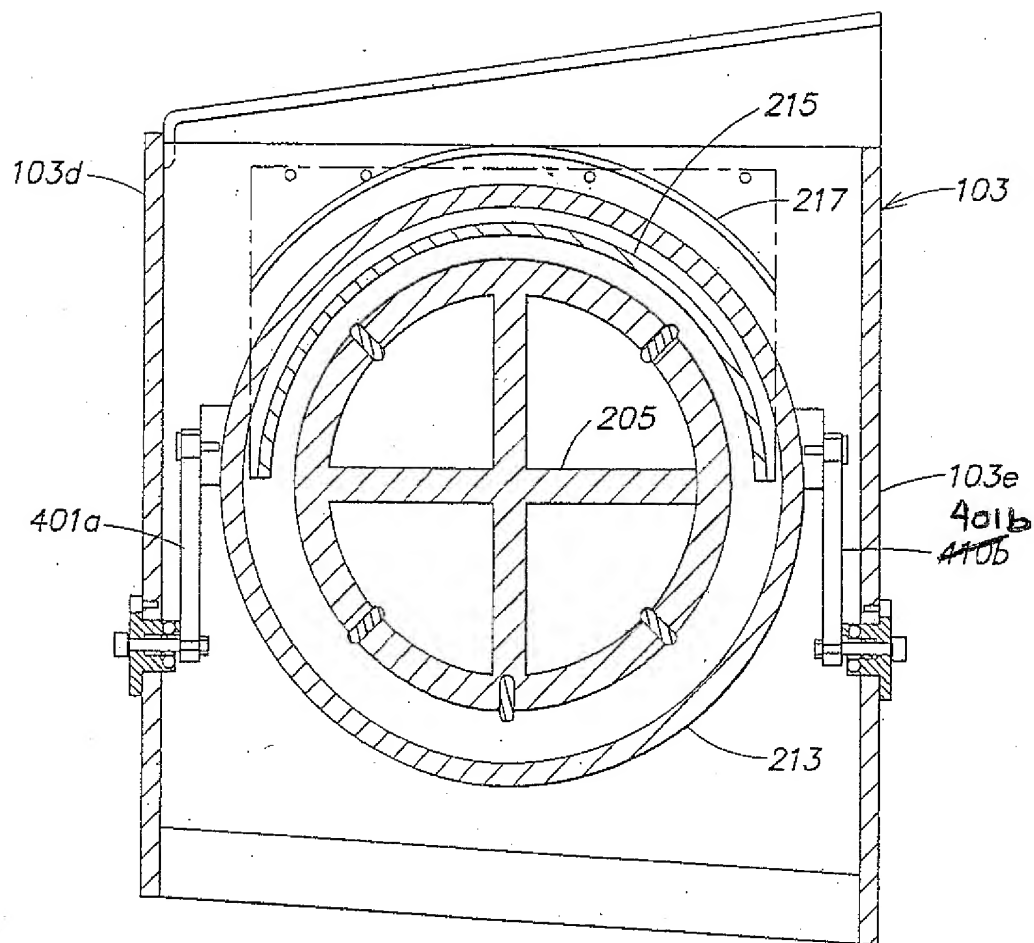


FIG. 4